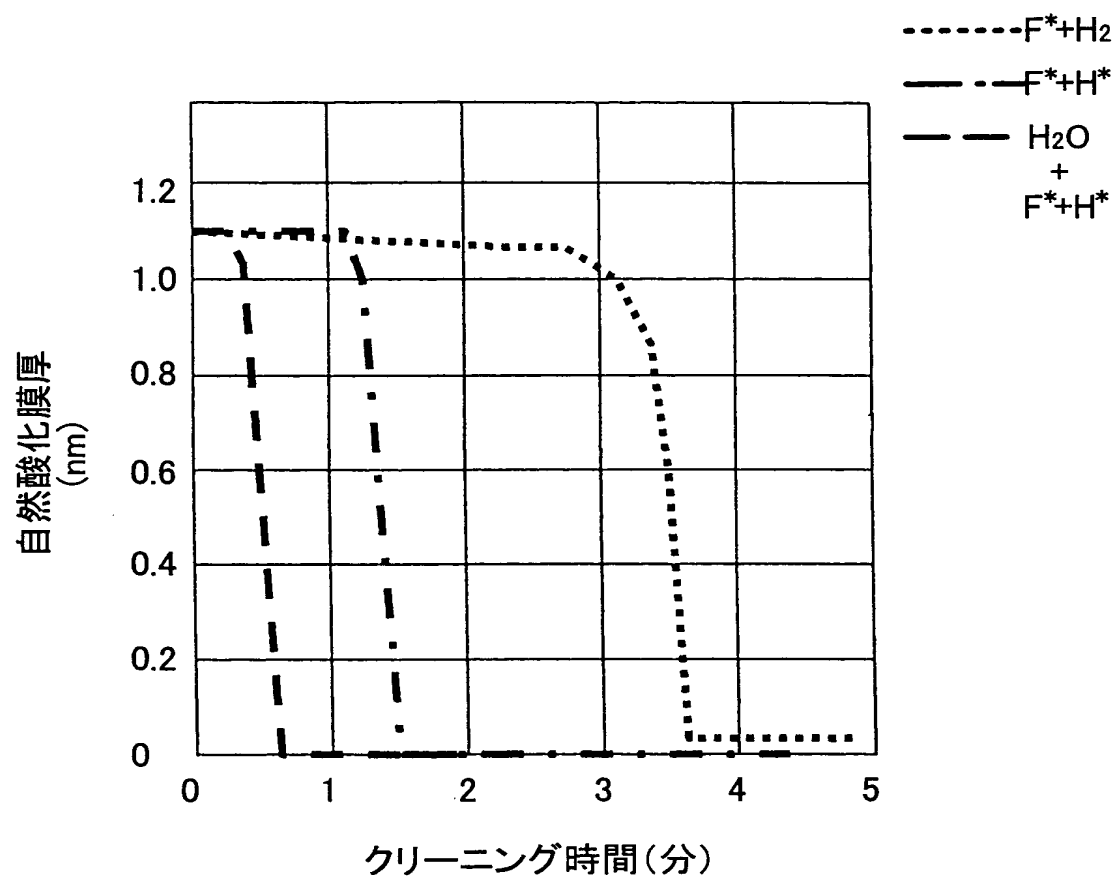
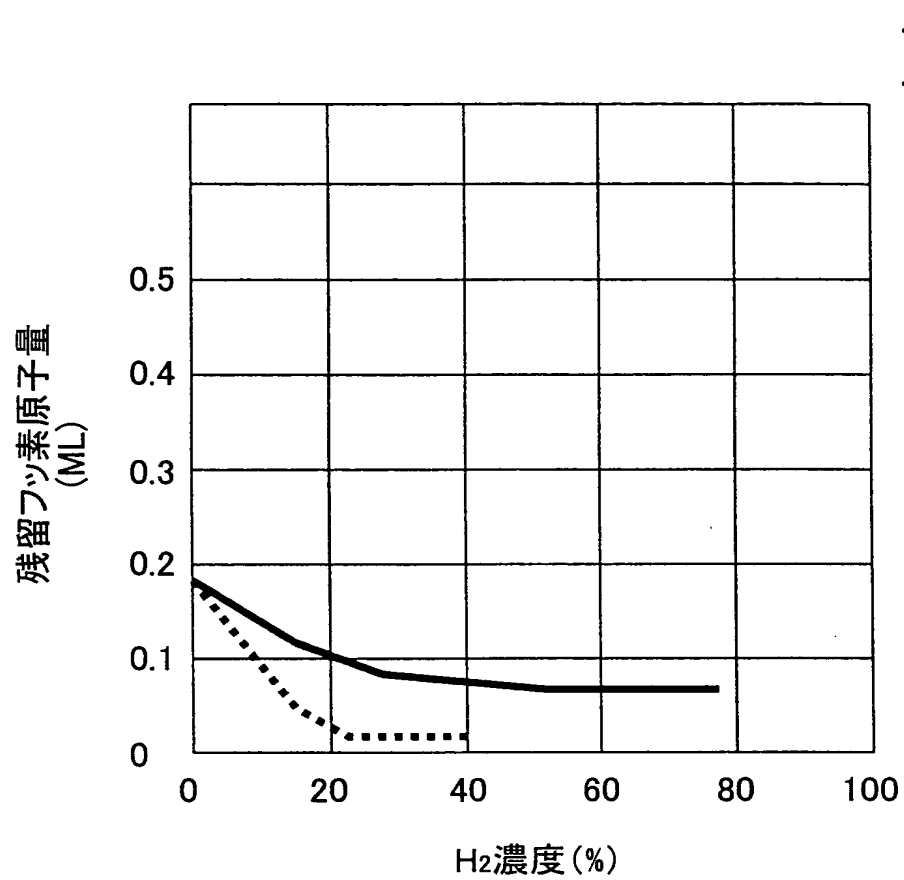


【図1】



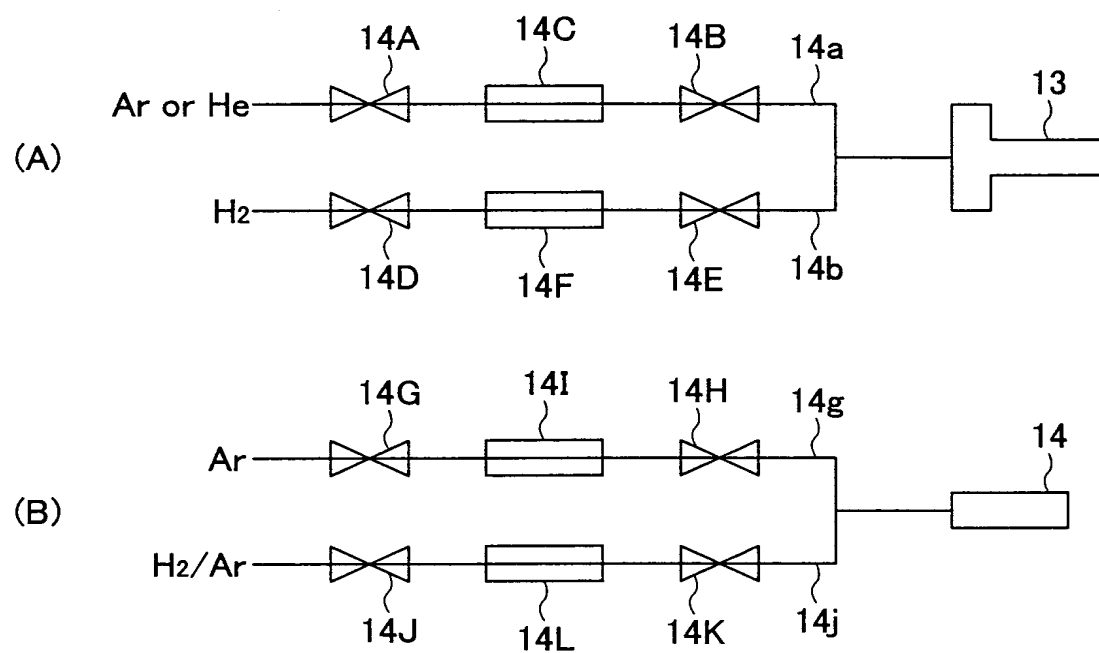
【図2】



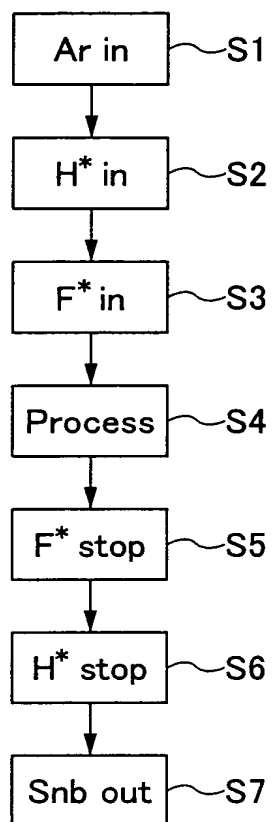
A cross-sectional diagram of a plasma processing apparatus. A central horizontal tube is labeled W . At its left end, there is a flange-like component labeled 14 , with a force vector F_2 pointing to the right. The tube passes through a series of vertical walls or partitions. On the far left, a box labeled 15 contains two circles, representing electrical connections. To the right of the tube, there are several vertical structures: a thick wall labeled $11A$, a thinner section labeled $11B$, another thick wall labeled $11C$, and a final section labeled $11D$. A double-headed arrow indicates movement between the $11C$ and $11D$ sections. Below the tube, there is a component labeled 12 and a base labeled 13 . Arrows indicate gas flow: $Ar+H_2$ enters from the bottom left, and three arrows point outwards from the right side of the chamber. Force vectors F^* and H^* are shown acting on the tube near the $11C$ section.

(B)

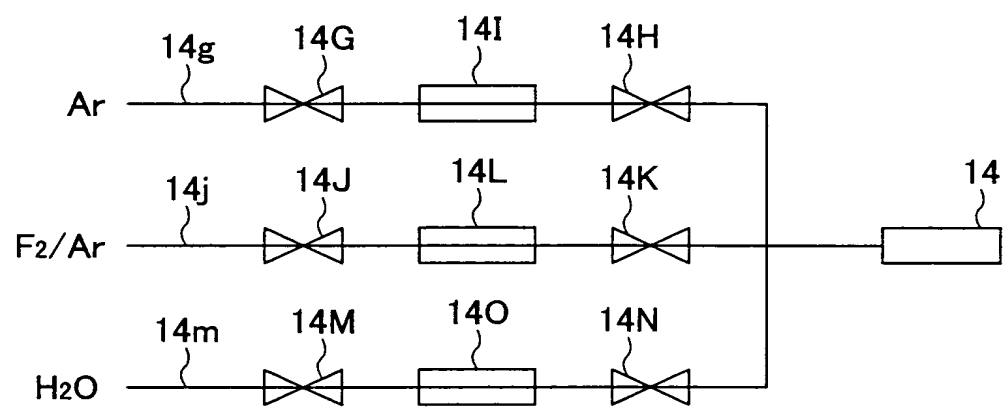
【図4】



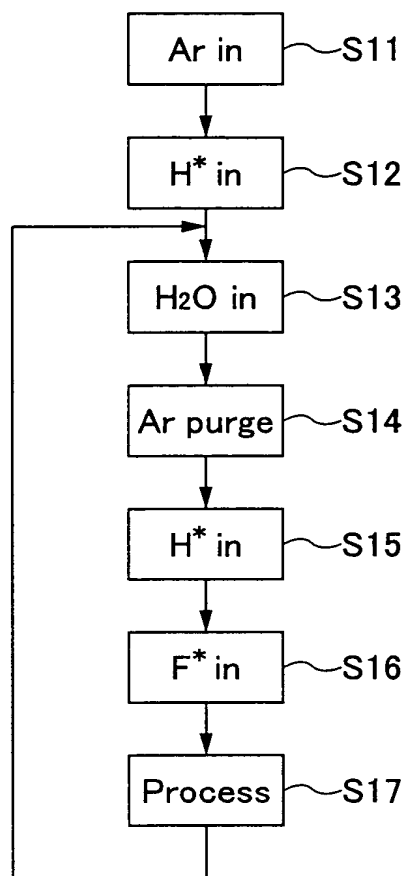
【図5】



【図6】



【図7】



【図8】

